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(21) International Application Number: PCT/US97/08008 (22) International Filing Date: 8 May 1997 (08.05.97) (30) Priority Data: 08/647,182 9 May 1996 (09.05.96) US (71) Applicant: APPLIED MATERIALS, INC. [US/US]; 3050 Bowers Avenue, Santa Clara, CA 95054 (US). (72) Inventors: SUBRAMANI, Anantha; 3098 Linkfield Way, San Jose, CA 95135 (US). FORSTER, John; 41 Hallam Street, San Francisco, CA 94103 (US). STIMSON, Bradley, O.; 1257 Hanchett Avenue, San Jose, CA 95126 (US). EDELSTEIN, Sergio; 117 El Altillo, Los Gatos, CA 95030 (US). GRUNES, Howard; 237 Trevethan Avenue, Santa Cruz, CA 95062 (US). TEPMAN, Avi; 21610 Rainbow Drive, Cupertino, CA 95014 (US). XU, Zheng; 270 Hudson Bay Street, Foster City, CA 94404 (US). (74) Agents: KONRAD, William, K. et al.; Loeb & Loeb LLP, Suite 2200, 10100 Santa Monica Boulevard, Los Angeles, CA 90067 (US).	(81) Designated States: JP, KR, SG, European patent (AT, BE, CH, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE). Published <i>With international search report.</i> <i>Before the expiration of the time limit for amending the claims and to be republished in the event of the receipt of amendments.</i>	

(54) Title: **RECESSED COIL FOR GENERATING A PLASMA**

(57) Abstract

A recessed coil for a plasma chamber in a semiconductor fabrication system is provided. Recessing the coil reduces deposition of material onto the coil which in turn leads to a reduction in particulate matter shed by the coil onto the workpiece.

